

Attorney Docket No.: YOR920030175US1

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Patent Application

Applicant(s): Allen et al.
Docket No.: YOR920030175US1
Serial No.: 10/661,041
Filed: September 12, 2003
Group: 2811
Examiner: Cuong Quang Nguyen

I hereby certify that this paper is being deposited on this date with the U.S. Postal Service as first class mail addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450

Signature: *John M. Munn* Date: February 23, 2005

Title: Techniques for Patterning Features in Semiconductor Devices

INFORMATION DISCLOSURE STATEMENT

Commissioner of Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. §§1.56, 1.97 and 1.98, Applicant's attorney wishes to bring to the attention of the Patent and Trademark Office the following document listed on the accompanying PTO Form 1449. Pursuant to 37 CFR §1.97(e)(1), each of the identified references were cited in a European Search Report dated December 17, 2004 (i.e., not more than three months prior to the filing of this Information Disclosure Statement).

U.S. Patent(s)

1. U.S. Patent No. 5,753,418
2. U.S. Patent No. 6,009,888
3. U.S. Patent No. 6,316,167
4. U.S. Patent No. 6,387,798
5. U.S. Patent No. 6,514,86

Copies of each of the following listed items are enclosed:

Foreign Document(s)

6. EP 0 236 220 A1

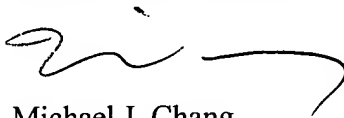
Other Document(s)

7. Celii et al., "Process Characterization for Tapered Contact Etch," J. Vac. Sci. Technol. B 19(5), American Vacuum Society, Pgs. 1845-1851 (Sept/Oct 2001).
8. Mahorowala et al., "Tunable Anti-Reflective Coatings with Built-In Hard Mask Properties Facilitating Thin Resist Processing," Proceedings of the SPIE, Vol. 4343, Pgs. 306-316 (2001).

In the event of non-payment or improper payment of a required fee, the Commissioner is authorized to charge or the credit **International Business Machines Corporation's Deposit Account No. 50-0510** as required to correct the error.

The filing of this Information Disclosure Statement shall not be construed as a representation that a search has been made, or as an admission that the information cited is considered to be material to patentability or as a representation that no other material information exists.

Respectfully submitted,



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Date: February 23, 2005

FORM PTO-1449 (MODIFIED)**LIST OF PUBLICATIONS FOR
APPLICANT'S INFORMATION
DISCLOSURE STATEMENT**

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U.S. PATENT DOCUMENTS

EXAMINER					FILING DATE
INITIAL	DOCUMENT NO.	DATE	NAME	CLASS/SUBCLASS	IF APPROPRIATE
_____	5,753,418	05/19/98	Tsai et al.	430/313	
_____	6,009,888	01/04/00	Ye et al.	134/1.3	
_____	6,316,167	11/13/01	Angelopoulos et al.	430/313	
_____	6,387,798	05/14/02	Loke et al.	438/623	
_____	6,514,867	02/04/03	Hui et al.	438/713	

FOREIGN PATENT DOCUMENTS

EXAMINER					TRANSLATION
INITIAL	DOCUMENT NO.	DATE	COUNTRY	CLASS/SUBCLASS	YES NO
_____	EP 0 236 220 A1	13/04/88	Europe		

OTHER DOCUMENTS

EXAMINER			
INITIAL	REF NO.	AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.	
_____		Celii et al., "Process Characterization for Tapered Contact Etch," J. Vac. Sci. Technol. B 19(5), American Vacuum Society, Pgs. 1845-1851 (Sept/Oct 2001).	
_____		Mahorowala et al., "Tunable Anti-Reflective Coatings with Built-In Hard Mask Properties Facilitating Thin Resist Processing," Proceedings of the SPIE, Vol. 4343, Pgs. 306-316 (2001).	

Examiner

Date Considered

Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.